

NPN 9 GHz wideband transistor crystal

X3A-BFR505

DESCRIPTION

NPN crystal used in BFR505 (SOT23), BFG505 (SOT143) and BFP505 (SOT173). Crystals are supplied as whole wafer, fully tested but unsawn.

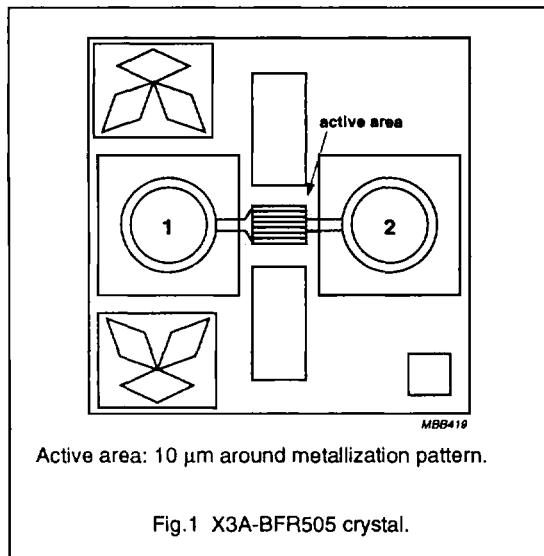
ELEMENT LAYOUT

Fig.1 X3A-BFR505 crystal.

MECHANICAL DATA

Crystal	
Top metallization	Au 1.15 µm
Back metallization	AuAs 0.35 µm
Passivation	Si ₃ N ₄ 0.5 µm
Base bond pad 1	dia. 55 µm
Emitter bond pad 2	dia. 55 µm
Collector contact	on underside of crystal
Wafer	
Diameter	76.1 mm (3 inches)
Crystal pitch	290 x 290 µm
Separation lane	60 µm
Sawing lane	50 µm
Slice thickness	200 ±15 µm
Average number of good elements per wafer	30 000
Faulty devices	inked out
Visual inspection	to URV-3-5-52/733

LIMITING VALUES

In accordance with the Absolute Maximum System (IEC 134).

SYMBOL	PARAMETER	CONDITIONS	MAX.	UNIT
V _{CBO}	collector-base voltage	open emitter	15	V
V _{CES}	collector-emitter voltage		15	V
V _{EBO}	emitter-base voltage	open collector	2.5	V
I _C	DC collector current		18	mA
T _j	junction temperature		150	°C

CHARACTERISTICS

SYMBOL	PARAMETER	CONDITIONS	MIN.	TYP.	MAX.	UNIT
I _{CBO}	collector cut-off current	I _E = 0; V _{CB} = 6 V	—	—	50	nA
h _{FE}	DC current gain	I _C = 5 mA; V _{CE} = 6 V	60	120	—	
f _T	transition frequency	I _C = 5 mA; V _{CE} = 6 V; f = 1 GHz	—	9	—	GHz
F	noise figure	I _C = 1.25 mA; V _{CE} = 6 V; f = 900 MHz	—	1.1	—	dB